

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Toshifumi NAGAIWA, et al.

SERIAL NO: 09/840,178

GAU: 1763

FILED FOR: April 24, 2001

EXAMINER: Ram N. KACKAR

WORKTABLE DEVICE AND PLASMA PROCESSING APPARATUS FOR SEMICONDUCTOR  
PROCESS

## REQUEST FOR CONTINUED EXAMINATION (RCE) TRANSMITTAL

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

SIR:

This is a request for Continued Examination (RCE) under 37 C.F.R. §1.114 of the above-identified application.

## Submission required under 37 C.F.R. §1.114

## Previously Submitted:

- ☒ Consider the amendment(s)/reply under 37 C.F.R. §1.116 previously filed on January 8, 2003
- ☐ Consider the arguments in the Appeal Brief or Reply Brief previously filed on

## Enclosed:

- ☒ Amendment/Reply
- ☐ Information Disclosure Statement (IDS)
- ☒ Other: Marked-up Copy, Request for Extension of Time (1 Month)

FEES	RATE	CALCULATIONS
<input type="checkbox"/> Suspension of action on the above-identified application is requested under 37 C.F.R. §1.103(c) for a period of _____ months.	\$130.00	\$0.00
<input checked="" type="checkbox"/> RCE Fee required under 37 C.F.R. §1.17(e)	\$750.00	\$750.00
<input checked="" type="checkbox"/> A ONE MONTH EXTENSION OF TIME IS REQUESTED		\$110.00
<input checked="" type="checkbox"/> Additional Claim Fees (if any)		\$0.00
TOTAL OF ABOVE CALCULATIONS:		\$860.00
<input type="checkbox"/> REDUCTION BY 50% FOR FILING AS SMALL ENTITY		\$0.00
TOTAL:		\$860.00

- ☒ A check in the amount of \$860.00 is enclosed

- ☒ Please charge any additional Fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to Deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.

- ☒ If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 CFR 1.136, and any additional fees required under 37 CFR 1.136 for any necessary extension of time may be charged to Deposit Account No. 15-0030. A duplicate of this sheet is enclosed.

Respectfully Submitted,

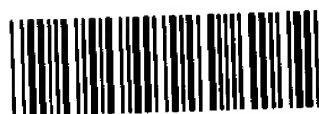
OBLON, SPIVAK, McCLELLAND,  
MAIER & NEUSTADT, P.C.

Gregory J. Maier

Registration No. 25,599

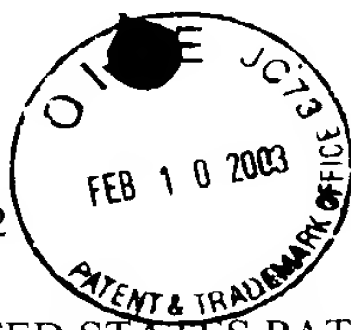
Carl E. Schlier

Registration No. 34,426



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IN RE APPLICATION OF

TOSHIFUMI NAGAIWA, ET AL.

SERIAL NO: 09/840,178

FILED: APRIL 24, 2001

FOR: WORKTABLE DEVICE AND  
PLASMA PROCESSING  
APPARATUS FOR  
SEMICONDUCTOR PROCESS

:

: EXAMINER: 1763

:

: GROUP ART UNIT: KACKAR, R.

:

AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

SIR:

Please amend the above-identified application as follows:

IN THE CLAIMS

Please amend the claims, as shown in the marked-up copy, to read as follows:

12. (Twice Amended) A worktable device for a semiconductor process, comprising:
- a worktable having a main surface for supporting a target substrate and a sub-surface disposed around said main surface;
  - a cooling mechanism disposed in said worktable and configured to supply cold to the main surface and the sub-surface;
  - a focus ring placed on the sub-surface and configured to surround the target substrate on the main surface;